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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of: Robert J. SMALL

Application No.: 10/802,780

Art Unit:

Filed: March 18, 2004

Examiner:

For: **RESIDUE REMOVERS FOR  
ELECTROHYDRODYNAMIC  
CLEANING OF SEMICONDUCTORS**

Atty Docket No.: 060937-0178-US

**INFORMATION DISCLOSURE STATEMENT**

U.S. Patent and Trademark Office  
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Sir:

In accordance with the duty of disclosure provisions of 37 C.F.R. §1.56, there is hereby provided certain information which the Examiner may consider material to the examination of the subject U.S. patent application. It is requested that the Examiner make this information of record if it is deemed material to the examination of the application.


Enclosed with this Information Disclosure Statement is a list of all patents, publications, applications, or other information submitted for consideration by the Office. There are thirteen (13) references listed in the above-referenced application, only the articles of which are submitted herewith. U.S. references will be provided upon request.

No fee is believed to be due for this submission, since this Information Disclosure Statement is being submitted before the first Office Action. Should any fees be required, however, please charge the required fees to Morgan, Lewis & Bockius LLP Deposit Account No. 50-0310.

Respectfully submitted,

July 30, 2004

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**LIST OF REFERENCES CITED BY APPLICANT**  
(Use several sheets if necessary)

ATTY DOCKET NO.

060937-0178

APPLICATION NO

10/802,780

APPLICANT

Robert J. SMALL

FILING DATE

march 18, 2004

GROUP

**U.S. PATENT DOCUMENTS**

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	A01	3,848,258	11/1974	Mahoney et al.			
	A02	3,893,131	07/1975	Perel et al.			
	A03	4,124,801	11/1978	Cook et al.			
	A04	4,264,641	04/1981	Mahoney et al.			
	A05	4,318,028	03/1982	Perel et al.			
	A06	4,462,806	07/1984	Mahoney et al.			
	A07	4,762,975	08/1988	Mahoney et al.			
	A08	4,835,383	05/1989	Mahoney et al.			
	A09	4,896,035	01/1990	Mahoney et al.			
	A10						

**FOREIGN PATENT DOCUMENTS**

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	B01							
	B02							
	B03							

**OTHER REFERENCES** (Including Author, Title, Date, Pertinent Pages, Etc.)

	C01	Journal of Vacuum Science & Technology B, "Dry Surface Cleaning Using CO <sub>2</sub> Snow" by Sherman et al., July/august 1991, pp 1970-1977
	C02	Journal of Vacuum Science & Technology A, "Carbon Dioxide Jet Spray Cleaning of Molecular Contaminants" by Hills, Jan/Feb. 1995, pgs.30-34
	C03	Particulate Science and Technology, Vol. 6, Number 2, 1988, "Methods for Surface Particle Removal: A Comparative Study" by Bardina
	C04	"Trends in Wafer Cleaning Technology" by Hattori, May 1995, Contamination Control, Wafer Cleaning
	C05	

**EXAMINER****DATE CONSIDERED**

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.